Form PTO-	449		ATTY. DOCKET NO. 29318US2			SERIAL NO. 10/809,092					
	INF		ON DISCLOSURE CITATION OF APPLICANT			APPLICANT: Min-Su Fung, et al.					
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VN	Α	4,236,165	4/1982	Szedon		_					
VN	В	4,812,756	3/1989	Curtis, et al	l.	_			_		
VN	С	5,216,362	6/1993	Verkuil							
VN	D	5,498,974	3/1996	Verkuil, et a	1.	_					
VN	Е	5,767,693	6/1998	Verkuil		•					
VN	F	5,834,941	11/1998	Verkuil, et a	1.						
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		OTHER REFERI	NCES (in	cluding Author Title	Date Pert	nent,	ages	, Eic)			
W	K	Solid State Technology, Test/Measurement, "Monitoring Electrically Active Contaminants to Assess Oxide Quality", Gregory S. Horner, et al., June 1985, PennWell Publishing Company, 4 Pages.									
VN	L	Semiconductor International, "A New Approach for Measuring Oxide Thickness", Tom G Miller, July 1995, Cahners Publishing Company, 2 Pages.									
VN	М	"COS Testing Combines Expanded Charge Monitoring Capabilities with Reduced Costs", Michael A. Peters, Semiconductor Fabtech 95, 4 Pages.									
VN	N	Process Monitoring, "Corona Oxide Semiconductor Test", Semiconductor Test Supplement, February/March 1995, Pages S-3 and S-5.									

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Initial if reference considered, regardless of whether citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

"QuantoxTM Non-Contact Oxide Monitoring System", John Bickley, 1995 Keithley Instruments, Inc., No. 1744, 6 Pages. (month lunar all hele)